

AMENDMENT

Sir:

In response to the Final Office Action of November 21, 2002, please amend the above-identified application as follows:

In the Claims:

Please amend claims 11 - 17 as follows:

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11. (TWICE AMENDED) A method for removing organic materials from a plurality of substrates having surface patterns with prominent sidewalls comprising the steps of:

providing an open tank containing a liquid chemical;
providing a quartz gas distribution plate submerged in said liquid chemical and supported horizontally by bottom of said tank;
providing a pressure regulated gas supply means connected to said gas distribution plate;
providing a substrate carrier containing a plurality of substrates;
submerging and resting said substrate carrier on said gas distribution plate so that said liquid chemical wets all surfaces of said substrates that are supported vertically within said substrate carrier;
said gas distribution plate generates and directs gas bubbles between and parallel to each surface of said substrates positioned thereabove, said gas bubbles providing a chemical-mechanical scrubbing.

12. (TWICE AMENDED) The method according to claim 11 wherein

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said quartz gas distribution plate having a top surface separated from a bottom surface, said bottom surface having a sinuous groove with a flexible tubing urged into and guided by said sinuous groove, each parallel leg of said sinuous groove having a multiplicity of holes formed through to said top surface, said holes are used as a drill jig guide for drilling prescribed diameter holes in each leg of said flexible tubing, said tubing having a first end connected to a gas supply means and a second end that is capped.

13. (TWICE AMENDED) The method according to claim 11 wherein said quartz gas distribution plate having a plurality of elongated slot openings extending from the top surface to the bottom surface contiguously disposed between said parallel segments, said slot openings traversing length of said plate, said slot openings facilitate tank cleaning and maintenance.

14. (TWICE AMENDED) The method according to claim 11 wherein using a quartz gas distribution plate eliminates photoresist residues in metal sidewalls that are coated with polymer.

15. (TWICE AMENDED) A method for stripping photoresist from a plurality of semiconductor wafers having top metal lines with prominent sidewalls, comprising the steps of:

- providing an open tank containing a liquid chemical;
- providing a quartz gas distribution plate submerged in said liquid chemical and supported horizontally by bottom of said tank;
- providing a pressure regulated gas supply means connected to said gas

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distribution plate;
providing a wafer cassette containing a plurality of wafers;
submerging and resting said wafer cassette on said gas distribution plate so
that said liquid chemical wets all surfaces of said wafers that are
supported vertically within said wafer cassette;
said gas distribution plate generates and directs gas bubbles between and
parallel to each surface of said wafers positioned thereabove, said gas
bubbles providing a chemical-mechanical scrubbing.

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16. (TWICE AMENDED) The method according to claim 15 wherein
said quartz gas distribution plate having a top surface separated from a bottom
surface, said bottom surface having a sinuous groove with a flexible tubing urged
into and guided by said sinuous groove, each parallel leg of said sinuous groove
having a multiplicity of holes formed through to said top surface, said holes are
used as a drill jig guide for drilling prescribed diameter holes in each leg of said
flexible tubing, said tubing having a first end connected to a gas supply means
and a second end that is capped.

17. (TWICE AMENDED) The method according to claim 15 wherein
said quartz gas distribution plate having a plurality of elongated slot openings
extending from the top surface to the bottom surface contiguously disposed
between said parallel segments, said slot openings traversing length of said
plate, said slot openings facilitate tank cleaning and maintenance.